

wherein said high frequency current includes frequencies which are more than 1 MHz, and said return plate is thicker than double an entering depth of the high frequency current and restrainable from vibrating the return plate due to the laser gas flow.

2. (Twice Amended) A laser apparatus comprising:

a laser chamber sealing a laser gas;

discharge electrodes constituted by a pair of anode and cathode provided within the laser chamber in an opposing manner, generating a discharge so as to excite a laser gas flowing therebetween and oscillating a laser beam;

a conductive anode base holding the anode;

an insulative cathode base holding the cathode;

a return plate electrically connecting the anode base to said laser chamber so as to supply a current to the anode; and

a high voltage power source supplying a high frequency current between the anode and the cathode;

wherein said high frequency current includes frequencies which are more than 1 MHz, and said return plate is thicker than double an entering depth of the high frequency current and restrainable from vibrating the return plate due to the laser gas flow;

wherein a thickness of the return plate is set to be equal to or more than 100 μm and equal to or less than 500 μm , and the return plate is arranged substantially in parallel to the laser gas flow between said discharge electrodes.